

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicants: YOSHIDA, et al

Serial No.: Rule 1.53(b) continuation of U.S. Patent  
Application Serial No. 09/581,814, filed June  
19, 2000

Filed: Herewith

For: ABRASIVE METHOD OF POLISHING TARGET MEMBER AND  
PROCESS FOR PRODUCING SEMICONDUCTOR DEVICE

Group of parent: 3723

Examiner of parent: D. Nguyen

PRELIMINARY AMENDMENT

Assistant Commissioner of Patents  
Washington, D.C. 20231

January 11, 2002

Sir:

Please amend the above-identified application, prior to  
examination thereof, as follows:

IN THE SPECIFICATION

Please amend the specification as follows:

Page 1, before line 1 "TECHNICAL FIELD", insert the  
following:

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--CROSS REFERENCE TO RELATED APPLICATIONS

This application is a Continuation Application of  
Application Serial No. 09/581,814, filed June 19, 2000.--

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